Hartmut Bracht

List of Publications by Year in descending order

Source: https://exaly.com/author-pdf/8952672/publications.pdf

Version: 2024-02-01

109321 123424 4,033 107 35 61 citations h-index g-index papers 107 107 107 1955 docs citations times ranked citing authors all docs

#	Article	IF	CITATIONS
1	Silicon Self-Diffusion in Isotope Heterostructures. Physical Review Letters, 1998, 81, 393-396.	7.8	303
2	Properties of intrinsic point defects in silicon determined by zinc diffusion experiments under nonequilibrium conditions. Physical Review B, 1995, 52, 16542-16560.	3.2	295
3	Intrinsic and extrinsic diffusion of phosphorus, arsenic, and antimony in germanium. Journal of Applied Physics, $2008,103,.$	2.5	188
4	Diffusion of <i>n</i> -type dopants in germanium. Applied Physics Reviews, 2014, 1, 011301.	11.3	146
5	Vacancy-mediated dopant diffusion activation enthalpies for germanium. Applied Physics Letters, 2008, 92, .	3.3	132
6	Diffusion and defect reactions between donors, C, and vacancies in Ge. I. Experimental results. Physical Review B, 2008, 77, .	3.2	117
7	Self-diffusion in germanium isotope multilayers at low temperatures. Applied Physics Letters, 2008, 93,	3.3	106
8	Self- and foreign-atom diffusion in semiconductor isotope heterostructures. II. Experimental results for silicon. Physical Review B, 2007, 75, .	3.2	105
9	Large disparity between gallium and antimony self-diffusion in gallium antimonide. Nature, 2000, 408, 69-72.	27.8	100
10	Diffusion Mechanisms and Intrinsic Point-Defect Properties in Silicon. MRS Bulletin, 2000, 25, 22-27.	3.5	92
11	Diffusion and solubility of copper, silver, and gold in germanium. Physical Review B, 1991, 43, 14465-14477.	3.2	91
12	Diffusion and defect reactions between donors, C, and vacancies in Ge. II. Atomistic calculations of related complexes. Physical Review B, 2008, 77, .	3.2	81
13	Diffusion of <i>E</i> centers in germanium predicted using GGA+ <i>U</i> approach. Applied Physics Letters, 2011, 99, 072112.	3.3	77
14	Vacancy-arsenic clusters in germanium. Applied Physics Letters, 2007, 91, .	3.3	75
15	Fluorine effect on As diffusion in Ge. Journal of Applied Physics, 2011, 109, .	2.5	73
16	Intrinsic and extrinsic diffusion of indium in germanium. Journal of Applied Physics, 2009, 106, .	2.5	72
17	Composition dependence of Si and Ge diffusion in relaxed Silâ^'xGex alloys. Journal of Applied Physics, 2010, 107, .	2.5	72
18	Radiation Enhanced Silicon Self-Diffusion and the Silicon Vacancy at High Temperatures. Physical Review Letters, 2003, 91, 245502.	7.8	71

#	Article	IF	CITATIONS
19	Atomic transport in germanium and the mechanism of arsenic diffusion. Materials Science in Semiconductor Processing, 2006, 9, 471-476.	4.0	71
20	Diffusion of silicon in crystalline germanium. Semiconductor Science and Technology, 2006, 21, 758-762.	2.0	71
21	Self- and foreign-atom diffusion in semiconductor isotope heterostructures. I. Continuum theoretical calculations. Physical Review B, 2007, 75, .	3.2	67
22	Copper related diffusion phenomena in germanium and silicon. Materials Science in Semiconductor Processing, 2004, 7, 113-124.	4.0	66
23	Defect interactions in Sn1â^'xGex random alloys. Applied Physics Letters, 2009, 94, 252104.	3.3	65
24	E centers in ternary Silâ^'xâ^'yGexSny random alloys. Applied Physics Letters, 2009, 95, .	3.3	64
25	Nonlinear stability of mmi:math xmins:mmi="http://www.w3.org/1998/Nath/Nath/Nath/Nath/Nath/Nath/Nath/Nath	3.2 <mml:mn></mml:mn>	63 >1
26	Fluorine codoping in germanium to suppress donor diffusion and deactivation. Journal of Applied Physics, 2009, 106, .	2.5	61
27	The vacancy in silicon: A critical evaluation of experimental and theoretical results. Journal of Applied Physics, 2008, 104, 076108.	2.5	58
28	Interstitial-Mediated Diffusion in Germanium under Proton Irradiation. Physical Review Letters, 2009, 103, 255501.	7.8	58
29	Double-hump diffusion profiles of copper and nickel in germanium wafers yielding vacancy-related information. Applied Physics Letters, 2000, 77, 642-644.	3.3	54
30	Phosphorous clustering in germanium-rich silicon germanium. Materials Science and Engineering B: Solid-State Materials for Advanced Technology, 2008, 154-155, 72-75.	3.5	51
31	Contributions of vacancies and self-interstitials to self-diffusion in silicon under thermal equilibrium and nonequilibrium conditions. Physical Review B, 2013, 88, .	3.2	49
32	Self- and interdiffusion in AlXGa1â^'XAs/GaAs isotope heterostructures. Applied Physics Letters, 1999, 74, 49-51.	3.3	43
33	Self-diffusion in crystalline silicon: A single diffusion activation enthalpy down to <mml:math xmlns:mml="http://www.w3.org/1998/Math/MathML"><mml:mrow><mml:mn>755</mml:mn><mml:msup><mml:width="0.16em"></mml:width="0.16em"><mml:mo>â~</mml:mo></mml:msup><mml:mi mathyariant="normal">C</mml:mi></mml:mrow></mml:math> . Physical Review B. 2016, 94.	inspace	41
34	P implantation into preamorphized germanium and subsequent annealing: Solid phase epitaxial regrowth, P diffusion, and activation. Journal of Vacuum Science & Technology B, 2008, 26, 430-434.	1.3	39
35	Zinc diffusion in gallium arsenide and the properties of gallium interstitials. Physical Review B, 2005, 71, .	3.2	38
36	Correlation between self-diffusion in Si and the migration mechanisms of vacancies and self-interstitials: An atomistic study. Physical Review B, 2008, 78, .	3.2	36

#	Article	IF	Citations
37	Diffusion and doping issues in germanium. Microelectronic Engineering, 2011, 88, 452-457.	2.4	33
38	Towards fabrication of 3D isotopically modulated vertical silicon nanowires in selective areas by nanosphere lithography. Microelectronic Engineering, 2017, 179, 74-82.	2.4	32
39	Enhanced and retarded Ga self-diffusion in Si and Be doped GaAs isotope heterostructures. Solid State Communications, 1999, 112, 301-314.	1.9	31
40	Self-diffusion in 69Ga121Sb/71Ga123Sb isotope heterostructures. Journal of Applied Physics, 2001, 89, 5393-5399.	2.5	28
41	Diffusion mediated by doping and radiation-induced point defects. Physica B: Condensed Matter, 2006, 376-377, 11-18.	2.7	27
42	Interstitial–Substitutional Diffusion Kinetics and Dislocation-Induced Trapping of Zinc in Plastically Deformed Silicon. Physica Status Solidi A, 1993, 137, 499-514.	1.7	26
43	Concentration of intrinsic defects and self-diffusion in GaSb. Journal of Applied Physics, 2008, 104, 093714.	2.5	25
44	Experiments and simulation on diffusion and activation of codoped with arsenic and phosphorous germanium. Journal of Applied Physics, 2010, 108, 024903.	2.5	25
45	A-centers and isovalent impurities in germanium: Density functional theory calculations. Materials Science and Engineering B: Solid-State Materials for Advanced Technology, 2011, 176, 453-457.	3.5	25
46	Zinc and gallium diffusion in gallium antimonide. Physical Review B, 2007, 75, .	3.2	24
47	Self-Diffusion in Isotopically Controlled Heterostructures of Elemental and Compound Semiconductors. Materials Research Society Symposia Proceedings, 1998, 527, 335.	0.1	21
48	Microscopic defects in silicon induced by zinc out-diffusion. Materials Science and Engineering B: Solid-State Materials for Advanced Technology, 2000, 71, 160-165.	3.5	21
49	Mechanism of zinc diffusion in gallium antimonide. Physica B: Condensed Matter, 2001, 308-310, 854-857.	2.7	21
50	Radiation-enhanced self- and boron diffusion in germanium. Physical Review B, 2013, 87, .	3.2	21
51	Thermal conductivity of isotopically controlled silicon nanostructures. New Journal of Physics, 2014, 16, 015021.	2.9	21
52	Simultaneous diffusion of Si and Ge in isotopically controlled heterostructures. Materials Science in Semiconductor Processing, 2008, 11, 378-383.	4.0	20
53	Suppression of donor-vacancy clusters in germanium by concurrent annealing and irradiation. Applied Physics Letters, $2011, 98, .$	3.3	20
54	Proton irradiation of germanium isotope multilayer structures at elevated temperatures. Journal of Applied Physics, 2008, 103, 033517.	2.5	18

#	Article	IF	Citations
55	Kinetics of Interstitial-Substitutional Exchange of Zn, Pt, and Au in Si: Experimental Results and Theoretical Calculations. Physica Status Solidi A, 1996, 158, 47-55.	1.7	17
56	Defect engineering in germanium. Physica Status Solidi (A) Applications and Materials Science, 2014, 211, 109-117.	1.8	16
57	Self-Diffusion in Amorphous Silicon by Local Bond Rearrangements. Physical Review Letters, 2018, 120, 225902.	7.8	16
58	Comment on "Self-Diffusion in Silicon: Similarity between the Properties of Native Point Defects― Physical Review Letters, 2000, 85, 4835-4835.	7.8	15
59	Out-diffusion of Zn from Si: A method to study vacancy properties in Si. Journal of Applied Physics, 1998, 83, 8062-8064.	2.5	14
60	Point defects in silicon after zinc diffusion - a deep level transient spectroscopy and spreading-resistance profiling study. Semiconductor Science and Technology, 1999, 14, 435-440.	2.0	14
61	Reduced thermal conductivity of isotopically modulated silicon multilayer structures. Applied Physics Letters, 2012, 101, 064103.	3.3	14
62	Impact of zinc halide addition on the growth of zinc-rich layers generated by sherardizing. Surface and Coatings Technology, 2015, 263, 66-77.	4.8	14
63	Doping dependence of self-diffusion in germanium and the charge states of vacancies. Applied Physics Letters, 2013, 102, .	3.3	13
64	Vacancy-donor complexes in highly <i>n</i> -type Ge doped with As, P and Sb. Journal of Physics Condensed Matter, 2016, 28, 335801.	1.8	13
65	Self- and foreign alkaline-earth diffusion in mixed cation silicate glasses. Solid State Ionics, 2009, 180, 109-115.	2.7	12
66	Zinc diffusion enhanced Ga diffusion in GaAs isotope heterostructures. Physica B: Condensed Matter, 2001, 308-310, 831-834.	2.7	11
67	Antisites and anisotropic diffusion in GaAs and GaSb. Applied Physics Letters, 2013, 103, 142107.	3.3	11
68	Phonon coherence in isotopic silicon superlattices. Applied Physics Letters, 2014, 105, 132104.	3.3	11
69	Quantitative scanning spreading resistance microscopy on n-type dopant diffusion profiles in germanium and the origin of dopant deactivation. Journal of Applied Physics, 2019, 125, .	2.5	11
70	A neutron reflectometry study on silicon selfâ€diffusion at 900 °C. Physica Status Solidi (B): Basic Research, 2012, 249, 2108-2112.	1.5	10
71	Molecular dynamics simulations of thermal transport in isotopically modulated semiconductor nanostructures. Physica Status Solidi (A) Applications and Materials Science, 2016, 213, 549-556.	1.8	10
72	Diffusion in isotopically controlled semiconductor systems. Physica B: Condensed Matter, 1999, 273-274, 981-986.	2.7	9

#	Article	IF	Citations
73	Structural and electrical properties of sol–gel derived Ge nanocrystals in SiO2 films. Applied Physics A: Materials Science and Processing, 2011, 103, 149-158.	2.3	9
74	Defect reactions in gallium antimonide studied by zinc and self-diffusion. Physica B: Condensed Matter, 2007, 401-402, 262-265.	2.7	8
75	Atomic transport during solid-phase epitaxial recrystallization of amorphous germanium. Applied Physics Letters, 2015, 107, .	3.3	8
76	Self-Holding Optical Actuator Based on a Mixed Ionic–Electronic Conductor Material. ACS Photonics, 2019, 6, 1182-1190.	6.6	8
77	Analysis of medium-range order based on simulated segmented ring detector STEM-images: amorphous Si. Ultramicroscopy, 2019, 200, 169-179.	1.9	8
78	Comparison of Experimental STEM Conditions for Fluctuation Electron Microscopy. Microscopy and Microanalysis, 2020, 26, 1100-1109.	0.4	8
79	Bodycote Prize WinnerSherardising – galvanising steel with zinc from vapour phase. International Heat Treatment and Surface Engineering, 2008, 2, 49-54.	0.2	7
80	Temperature dependence of ion-beam mixing in crystalline and amorphous germanium isotope multilayer structures. Journal of Applied Physics, 2014, 115, 023506.	2.5	7
81	Microstructural Studies of Fluorineâ€∢scp>Implanted Titanium Aluminides for Enhanced Environmental Durability. Advanced Engineering Materials, 2014, 16, 52-59.	3.5	7
82	lon-Beam-Induced Atomic Mixing in Ge, Si, and SiGe, Studied by Means of Isotope Multilayer Structures. Materials, 2017, 10, 813.	2.9	7
83	Self-diffusion in single crystalline silicon nanowires. Journal of Applied Physics, 2018, 123, 161515.	2.5	7
84	Focused Ion Beam Sample Preparation for <i>In Situ</i> Thermal and Electrical Transmission Electron Microscopy. Microscopy and Microanalysis, 2021, 27, 828-834.	0.4	7
85	Advanced dopant and self-diffusion studies in silicon. Nuclear Instruments & Methods in Physics Research B, 2006, 253, 105-112.	1.4	6
86	Determination of nanoscale heat conductivity by time-resolved X-ray scattering. Thin Solid Films, 2013, 541, 28-31.	1.8	6
87	Ion-beam induced atomic mixing in isotopically controlled silicon multilayers. Journal of Applied Physics, 2016, 120, 185701.	2.5	6
88	Ion-beam mixing in crystalline and amorphous germanium isotope multilayers. Journal of Applied Physics, 2011, 110, 093502.	2.5	5
89	Properties of Point Defects in Silicon: New Results after a Long-Time Debate. Solid State Phenomena, 0, 205-206, 151-156.	0.3	5
90	Ultrafast study of phonon transport in isotopically controlled semiconductor nanostructures. Physica Status Solidi (A) Applications and Materials Science, 2016, 213, 541-548.	1.8	5

#	Article	IF	CITATIONS
91	Fluctuation electron microscopy on silicon amorphized at varying self ion-implantation conditions. Journal of Applied Physics, 2019, 126, 095707.	2.5	5
92	Defect distribution in boron doped silicon nanostructures characterized by means of scanning spreading resistance microscopy. Journal of Applied Physics, 2020, 127, .	2.5	5
93	Reply to "Comment on â€~Contributions of vacancies and self-interstitials to self-diffusion in silicon under thermal equilibrium and nonequilibrium conditions' ― Physical Review B, 2014, 90, .	3.2	4
94	Light absorption in Ge nanoclusters embedded in SiO2: comparison between magnetron sputtering and sol–gel synthesis. Applied Physics A: Materials Science and Processing, 2014, 116, 233-241.	2.3	4
95	Dynamics of Network Formers and Modifiers in Mixed Cation Silicate Glasses. Zeitschrift Fur Physikalische Chemie, 2010, 224, 1677-1705.	2.8	3
96	Cation diffusion in mixed cation silicate glasses under non-equilibrium conditions. Solid State Ionics, 2012, 222-223, 47-52.	2.7	3
97	Response to "Comment on â€~Diffusion of n-type dopants in germanium' ―[Appl. Phys. Rev. 2, 0361 Applied Physics Reviews, 2015, 2, 036102.	.01 (2015 11.3)] ₃
98	Structural and Thermal Characterisation of Nanofilms by Time-Resolved X-ray Scattering. Nanomaterials, 2019, 9, 501.	4.1	3
99	Diffusion of boron in germanium at 800–900 °C revisited. Journal of Applied Physics, 2020, 127, 025703.	2.5	3
100	Impact of oxygen on gallium doped germanium. AIP Advances, 2021, 11, 065122.	1.3	3
101	Atomistic simulations on the relationship between solid-phase epitaxial recrystallization and self-diffusion in amorphous silicon. Journal of Applied Physics, 2022, 131, .	2.5	3
102	Diffusion and Point Defects in Silicon Materials. Lecture Notes in Physics, 2015, , 1-67.	0.7	2
103	Measurement and analysis of thermal conductivity of isotopically controlled silicon layers by timeâ€resolved Xâ€ray scattering. Physica Status Solidi (A) Applications and Materials Science, 2016, 213, 3020-3028.	1.8	2
104	Electrochemical Proton Intercalation in Vanadium Pentoxide Thin Films and its Electrochromic Behavior in the nearâ€IR Region. ChemistryOpen, 2021, 10, 340-346.	1.9	2
105	Properties of Vacancies in Silicon Determined by Out-Diffusion of Zinc from Silicon. Materials Research Society Symposia Proceedings, 1998, 532, 219.	0.1	1
106	Thermal transport across isotopic 28Si/mSi interfaces. Computational Materials Science, 2017, 139, 354-360.	3.0	1
107	Retarded boron and phosphorus diffusion in silicon nanopillars due to stress induced vacancy injection. Journal of Applied Physics, 2022, 131, 075702.	2.5	1